

## ABSTRACT OF THE DISCLOSURE

A corrected mask pattern verification apparatus includes a graphic operation section for generating  
5 differential mask pattern data based on design mask pattern  
and corrected mask pattern; a graphic  
reduction-enlargement operation section for reducing the  
differential mask pattern data and enlarging the reduced  
differential mask pattern data, and generating graphic  
10 reduction-enlargement operation data; and an area  
comparison operation section for calculating an area of  
a differential mask pattern represented by the  
differential mask pattern data and comparing the  
calculated area with a prescribed area, and generating  
15 area comparison operation data indicating an area  
comparison operation result.